## **EAST Search History**

## EAST Search History (Prior Art)

Ref#	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	4	(("5757477") or ("6482661")).PN	US PGPUB; USPAT; EPO; JPO; DERWENT; BM_TDB	OR	OFF	2010/11/22 09:54
S1	2124	sheela chawan. Xa.	US PGPUB; USPAT; EPO; JPO; DERWENT; BM_TDB	OR	ON	2010/03/09 15:40
\$2	2338	sheela chawan Xp.	US PGPUB; USPAT; EPO; JPO; DERWENT; BM_TDB	OR	ON	2010/03/09 15:46
S3	2	SI and wafer adj polishing	US PGPUB; USPAT; EPO; JPO; DERWENT; BM_TDB	OR	ON	2010/03/09 15:46
S4	2	S2 and wafer adj polishing	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/09 15:47
S5	22	S1 and wafer adj inspection	US-PGPUB; USPAT; EPO; UPO; DERWENT; IBM_TDB	OR	ON	2010/03/09 15:48

S6	22	S2 and wafer adj inspection	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/09 15:48
57	156	wafer adj pad and inspection	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/09 16:05
S8	156	wafer adj pad and inspection	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 16:04
S9	27	S3 and notch	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 16:04
S10	337122	crystallographic asj structure and wafer	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 16:09
S11	966	crystallographic adj structure and wafer	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 16:09
S12	191	crystallographic adj structure same wafer	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 16:09
S13	150	\$12 and (@ad<"20040202" or @rlad<"20040202" or @prad<"20040202" or @ptad<"20040202")	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 16:21

S14	117	S12 and @ad<"20040202"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 16:21
S15	16	S14 and(solar adj cell or cell)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 16:22
S16	16	S15 and (compar\$3 or match\$3)and wafer and(solar adj cell or cell)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 16:23
S17	41	crystallographic adj structure and wafer and ingot	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 16:39
S18	5	S17 and(compar\$3 or match\$3)and wafer and(solar adj cell or cell)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 16:40
S19	4	S18 and @ad<"20040202"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 16:40
\$20	110	(("(4352948") or ("6161054") or ("5203005") or ("5287472") or ("5292677") or ("5485097") or ("6243308") or ("4435498") or ("4471483") or ("4499055") or ("4519035") or ("4543444") or ("4898335") or ("499689") or ("5019736") or ("5024972") or ("5252507") or ("5265847") or ("5361530") or ("5362666") or ("5393817") or ("5478363") or ("5491665") or ("5536964") or ("552243") or ("5619419") or ("5624771") or ("5666392") or ("5657284") or ("5698453") or ("5698342") or ("5716459") or ("5898947") or ("58986453") or ("6040912") or ("6140140") or ("6161213") or ("6225167") or ("6330819") or ("4304644") or ("4333480") or ("4353160") or ("4385198") or ("4400221") or ("4400868") or (").pn.")).	US-PGPUB; USPAT; EPO; JPO; DERWENT; BM_TDB	ÖR	OFF	2010/03/10 16:43

S21	106	\$20 and(@ad<"20040202" or @rlad< "20040202" or @prad<"20040202" or @ptad<"20040202")	US-PGPUB; USPAT; EPO; JPO; DERWENT; BM_TDB	OR	ON	2010/03/10 16:43
S22	106	\$20 and @ad<"20040202"	US-PGPUB; USPAT; EPO; JPO; DERWENT; BM_TDB	OR	ON	2010/03/10 16:43
\$23	0	S22 and crystallographic adj structure and wafer and ingot	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 16:44
224	0	S22 and crystallographic adj structure and wafer and ingot	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 16:46
325	5	\$22 and inspect\$3 and(crystallographic adj structure or wafer or ingot or cells or cell)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 17:05
526	4	\$25 and(compar\$3 or match\$3) and(solar adj cell or cell crystallographic adj structure or wafer or ingot or cells or cell)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 17:06
\$27	4	\$26 and @ad< "20040202"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 17:07
S28	4742	crystallographic adj structure	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM TDB	OR	ON	2010/03/10 17:10

S29	4328355	(wafer\$1 or semiconductor or solar adj cell or cell)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 17:11
S30	98638	S29 and inspect\$3 and(cells or cell)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 17:20
S31	153527	S29 and inspect\$3 and(cells or cell or wafer or memory)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 17:21
S32	4742	crystallographic adj structure	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 17:22
333	632	S31 and S32	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 17:27
534	1	S33 and wafer adj image and cell adj image	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 17:28
S35	3	inspect\$3 and solar adj cell and matrix and convert\$3 and electricity and solar adj cell and treating and silicon adj wafers and ingot	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 17:32
336	2	S35 and @ad< "20040202"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 17:33

337	1	S35 and (compar\$3 or match\$3)and wafer adj image and cell adj image	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 17:39
338	1	S32 and wafer adj image and cell adj image	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 17:40
339	17	S29 and (compar\$3 or match\$3)and wafer adj image and cell adj image	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 17:40
340	3	339 and @ad< "20040202"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 17:41
341	1	S39 and crystallographic adj structure	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 17:51
342	1	\$39 and crystallographic adj structure and wafer adj structure and imanufactured adj cell and crystallographic adj image and information and sufficient adj establish and correspondence and cell and wafer	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 17:58
343	1	\$39 and crystallographic adj structure and wafer adj structure and manufactured adj cell	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 17:59
344	1	crystallographic adj structure and wafer adj structure and manufactured adj cell	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM TDB	OR	ON	2010/03/10 17:59

S45	2	S29 and crystallographic adj structure and manufactured adj cell	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 18:00
S46	0	\$45 and @ad<"20040202"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 18:01
S48	607	S32 and inspect\$3 and(cells or cell or memory)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 18:06
S49	1	S48 and wafer adj image and cell adj image	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 18:06
S50	587	\$48 and(compar\$3 or match\$3)and (memory or cell or memory adj cell)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 18:07
351	1	\$48 and(compar\$3 or match\$3)same(memory or cell or memory adj cell) same wafer\$1	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 18:08
S52	1	\$50 and crystallographic adj structure and wafer adj structure and manufactured adj cell	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 18:09
S53	1	S50 and wafer adj structure and manufactured adj cell	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 18:09

354	1	S0 and manufactured adj cell	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 18:10
355	297	S50 and @ad< "20040202"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 18:10
S56	12	\$55 and(compar\$3 or match\$3)and wafer and(solar adj cell or cell)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 18:11
S57	13	\$55 and inspect\$3 and wafer\$1 and(cells or cell or memory)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 18:12
S58	0	S55 and inspect\$3 adj wafer\$1 same(cells or cell or memory)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 18:13
S59	0	\$55 and inspect\$3 adj wafer\$1 and(cells or cell or memory)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 18:13
\$60	3559	\$28 and(wafer\$1 or semiconductor or solar adj cell or cell or memory)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 18:14
S61	2	S60 and manufactured adj cell	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 18:14

362	0	S61 and @ad< "20040202"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 18:14
363	2	S32 and manufactured adj cell	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 18:15
364	1818	S32 and(wafer\$1 or semiconductor or memory)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 18:16
365	237	S32 and(wafer\$1 or semiconductor or memory)and inspect\$3	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 18:16
366	119	S65 and @ad<"20040202"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 18:16
367	12	956 and(compar\$3 or match\$3)and wafer and(solar adj cell or cell)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 18:19
368	38	\$32 and inspect\$3 and(compar\$3 or match\$3) and wafer and(solar adj cell or cell)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 18:28
369	41	\$32 and inspect\$3 and(compar\$3 or match\$3)and wafer and(solar adj cell or cell or memory)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM TDB	OR	ON	2010/03/10 18:29

S70	13	\$69 and @ad<"20040202"	US-PGPUB; USPAT; EPO; JPO; DERWENT; BM_TDB	OR	ON	2010/03/10 18:29
571	85837	analyz\$3 and(crystalline or crystallographic adj structure)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 18:35
572	18	S71 and manufactured adj cell	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 18:36
573	1	\$72 and(wafer\$1 or semiconductor or memory)and inspect\$3	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 18:36
574	1	inspect\$3 and photovoltaic adj area and manufactured and crystalline adj cell	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 18:43
575	0	S74 and @ad<"20040202"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 18:44
S76	0	S72 and(imaging or ccd or camera or CMOS or IR)and wafer adj image and cell adj image	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 18:46
577	0	S71 and(imaging or cod or camera or CMOS or IR)and wafer adj image and cell adj image	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 18:47

S78	31037	S71 and(imaging or ccd or camera or CMOS or IR)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 18:47
S79	8	S78 and manufactured adj cell	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 18:47
S80	2	S79 and @ad< "20040202"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 18:48
S81	2106	\$78 and(wafer\$1 or semiconductor\$1 or IC or intergrated adj circuit) and inspect\$3	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 18:51
382	45	\$31 and(compar\$3 or match\$3)same(memory or cell or memory adj cell) same wafer\$1	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 18:52
383	18	S82 and @ad<"20040202"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 18:52
S84	25	S17 and @ad< "20040202"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 19:17
385	5	S72 and @ad<"20040202"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 19:48

586	118795	(wafer\$1 or semiconductor\$1 or IC or intergrated adj circuit) and inspect\$3	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 19:49
387	9	\$36 and(imaging or ccd or camera or CMOS or IR)and wafer adj image and cell adj image	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 19:49
S88	1	\$37 and @ad<"20040202"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 19:49
389	533	crystallographic adj structure and(wafer or ingot) and section	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 20:15
390	161	\$89 and analyz\$3 and(crystalline or crystallographic adj structure)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 20:16
391	0	\$39 and analyz\$3 and(crystalline or crystallographic adj structure) same ignot	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 20:16
392	0	S90 and(imaging or ccd or camera or CMOS or IR)and wafer adj image	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 20:17
393	120	S90 and(imaging or ccd or camera or CMOS or IR)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 20:17

394	48	S93 and @ad<"20040202"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 20:22
395	0	S93 and etching and texturisation	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 20:59
S96	7	(wafer\$1 or semiconductor\$1 or IC or intergrated adj circuit) and etching and texturisation and inspect\$3	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 21:00
S97	2	S96 and @ad< "20040202"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 21:00
S98	0	\$97 and(compar\$3 or match\$3)same(memory or cell or memory adj cell or idie)same wafer\$1	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 21:01
599	0	\$97 and(compar\$3 or match\$3)and(memory or cell or memory adj cell or idie)and wafer\$1	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 21:01
S100	2	\$97 and(memory or cell or memory adj cell or die)and wafer\$1	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 21:01
S101	161	S39 and S90	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM TDB	OR	ON	2010/03/10 21:05

S102	0	\$101 and(wafer\$1 or semiconductor\$1 or IC or intergrated adj circuit)and etching and texturisation and inspect\$3	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 21:06
S103	0	S101 and etching and texturisation and inspect\$3	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 21:06
S104	0	S101 and etching and texturisation	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 21:07
\$105	1	S99 and etching and texturisation	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 21:07
S106	20	S99 and solar adj cell	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 21:08
S107	8	S106 and @ad< "20040202"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 21:08
S108	2468	ingot and production adj process	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 21:10
S109	523	\$108 and wafer\$3 and production adj process	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 21:11

S110	128	S109 and cell and production adj process	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 21:11
S111	1	S110 and wafer adj position\$3	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 21:12
S112	75	S110 and @ad<"20040202"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 21:13
S113	0	S112 and cell adj inspect\$3	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 21:13
S114	75	S112 and(memory or cell or memory adj cell or die)and wafer\$1	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 21:14
S115	0	S114 and(imaging or cod or camera or CMOS or IR)and wafer adj image	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 21:14
S116	12	S114 and(imaging or cod or camera or OMOS or IR)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 21:14
S117	10	\$116 and(compar\$3 or match\$3)and(memory or cell or memory adj cell or die)and wafer\$1	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 21:15

S118	10	S117 and @ad<"20040202"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/10 21:15
S119	93	measur\$3 and polycrystalline adj wafer\$1	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/11 10:04
S120	63	photovoltaic adj devices and(slicing or dice\$3 or diced)and ingot	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/11 10:05
S121	0	idefect adj characteriz\$3 and classificat\$3 and crystal adj growth and ingot	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/11 10:07
S122	54	defect and classificat\$3 and crystal adj growth and ingot	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/11 10:08
S123	0	(defects or grain adj boundaries)and processing adj wafer\$1 and classificat \$3 and crystal adj growth and ingot	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/11 10:09
S124	75	(defects or grain adj boundaries) and processing adj wafer\$1 and crystal adj growth and ingot	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/11 10:10
S125	3	S119 and S120	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/11 10:10

S126	0	S124 and S125	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/11 10:11
S127	0	S125 and(defects or grain adj boundaries)and crystal adj growth and ingot	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/11 10:11
S128	0	S125 and(defects or grain adj boundaries)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/11 10:12
S129	0	S125 and defects and crystal adj growth and ingot	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/11 10:12
S130	10	S120 and(imaging or cod or camera or CMOS or IR)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/11 10:15
S131	3	S130 and @ad<"20040202"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/11 10:16
S132	0	S120 and inspect\$3 adj defects and crystal adj growth and ingot	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/11 10:29
S133	0	\$120 and inspect\$3 and defects and crystal adj growth and ingot	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM TDB	OR	ON	2010/03/11 10:29

S134	4	S120 and inspect\$3	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/11 10:30
S135	1	S134 and(defects or grain adj boundaries)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/11 10:30
S136	0	S135 and @ad<"20040202"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/11 10:30
S137	55	S120 and(defects or variances or voids or defects or stacking adj faults or inclusions or impurities or grain or crystal adj boundaries)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/11 10:35
S138	1	S137 and(imaging or cod or camera or CMOS or IR)and surface adj wafer\$1	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/11 10:35
S139	0	\$138 and @ad<"20040202"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/11 10:36
S140	55	S120 and S137	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/11 10:36
S141	20	S140 and @ad<"20040202"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM TDB	OR	ON	2010/03/11 10:36

S142	13	S141 and(compar\$3 or match\$3)and(wafer or ingot or cells or cell)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/11 10:44
S143	11	\$141 and(compar\$3 or match\$3)same(wafer or ingot or cells or cell)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/11 10:46
S144	11	S143 and @ad<"20040202"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/11 10:46
S145	0	S141 and(imaging or cod or camera or CMOS or IR)and wafer adj image and cell adj image	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/11 10:49
S146	0	\$141 and(imaging or cod or camera or CMOS or IR)and wafer adj image and cell adj image and(compar\$3 or match\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/11 10:50
S147	0	\$137 and(imaging or cod or camera or CMOS or IR)and wafer adj image and cell adj image and(compar\$3 or match\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/11 10:50
S148	0	\$120 and(imaging or cod or camera or CMOS or IR)and wafer adj image and cell adj image and(compar\$3 or match\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/11 10:51
S149	0	\$120 and(imaging or cod or camera or CMOS or IR)and wafer adj image and cell adj image and(compar\$3 or match\$3)and surface adj wafer\$1	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/11 10:51

S150	0	S119 and(imaging or cod or camera or CMOS or IR)and wafer adj image and cell adj image and(compar\$3 or match\$3)and surface adj wafer\$1	US-PGPUB; USPAT; EPO; JPO; DERWENT; BM_TDB	OR	ON	2010/03/11 10:52
S151	0	\$124 and(imaging or cod or camera or CMOS or IR)and wafer adj image and cell adj image and(compar\$3 or match\$3)and surface adj wafer\$1	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/11 10:52
S152	0	\$120 and(imaging or cod or camera or CMOS or IR)and(compar\$3 or match \$3) and surface adj wafer\$1	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/11 10:53
S153	5	(imaging or cod or camera or CMOS or IR)and(compar\$3 or match\$3)and photovoltaic adj devices and(slicing or dice\$3 or diced)and ingot	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/11 10:54
S154	2	S153 and @ad<"20040202"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/11 10:54
S155	2	S154 and(defects or variances or voids or defects or stacking adj faults or inclusions or impurities or grain or crystal adj boundaries)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/11 10:55
S156	4	\$120 and(wafer\$1 or semiconductor\$1 or IC or intergrated adj circuit) and inspect\$3	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/11 11:04
S157	10	\$119 and(wafer\$1 or semiconductor\$1 or IC or intergrated adj circuit) and inspect\$3	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM TDB	OR	ON	2010/03/11 11:04

S158	0	\$156 and(imaging or cod or camera or CMOS or IR)and wafer adj image and cell adj image and(compar\$3 or match\$3)and surface adj wafer\$1	US-PGPUB; USPAT; EPO; JPO; DERWENT; BM_TDB	OR	ON	2010/03/11 11:04
S159	0	\$156 and(imaging or cod or camera or CMOS or IR)and wafer adj image and cell adj image and(compar\$3 or match\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/11 11:05
S160	0	\$157 and(imaging or cod or camera or CMOS or IR)and wafer adj image and cell adj image and(compar\$3 or match\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/11 11:05
S161	0	\$157 and(imaging or cod or camera or CMOS or IR)and(compar\$3 or match \$3) and photovoltaic adj devices and(slicing or dice\$3 or diced) and ingot	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/11 11:05
S162	0	\$157 and(imaging or cod or camera or CMOS or IR)and(compar\$3 or match \$3)and (cell adj solar or cell or memory or wafer\$1)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/11 11:06
5163	4	S157 and(imaging or ccd or camera or CMOS or IR)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/11 11:06
S164	4	S163 and @ad< "20040202"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/11 11:06
S165	1	S164 and(defects or variances or voids or defects or stacking adj faults or inclusions or impurities or grain or crystal adj boundaries)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM TDB	OR	ON	2010/03/11 11:07

S166	0	S119 and produc\$4 and wafer adj image and cell adj image	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/11 11:16
S167	0	\$120 and produc\$4 and wafer adj image and cell adj image	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/11 11:16
S168	0	\$122 and produc\$4 and wafer adj image and cell adj image	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/11 11:16
3169	0	S122 and(produc\$4 or obtaining)and wafer adj image and cell adj image	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/11 11:16
\$170	0	\$157 and(produc\$4 or obtaining)and wafer adj image and cell adj image	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/11 11:17
3171	0	S153 and(produc\$4 or obtaining)and wafer adj image and cell adj image	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/11 11:17
5172	0	S155 and(produc\$4 or obtaining)and wafer adj image and cell adj image	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/11 11:17
S173	1	crystallographic adj structure and(produc\$4 or obtaining)and wafer adj image and cell adj image and wafer	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/11 11:18

S174		crystallographic adj structure and(produc\$4 or obtaining)and wafer adj image and(cell adj image or cells or cell or wafer or memory)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/11 11:20
S175	3130	crystallographic adj structure and(produc\$4 or obtaining)and(cell adj image or cells or cell or wafer or memory)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/11 11:20
S176	2	\$175 and photovoltaic adj devices and(slicing or dice\$3 or diced)and ingot	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/11 11:21
S177	2	S176 and @ad< "20040202"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/11 11:21
S178	0	S177 and(imaging or cod or camera or CMOS or IR or image)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/11 11:31
S179	1586	S175 and(imaging or ccd or camera or CMOS or IR or image)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/11 11:31
S180	0	\$179 and photovoltaic adj devices and(slicing or dice\$3 or diced)and ingot	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/11 11:32
S181	0	\$179 and photovoltaic adj devices and(slicing or dice\$3 or diced)and (ingot or wafer\$1 or semiconductor\$1 or IC or intergrated adj circuit)and inspect \$3	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM TDB	OR	ON	2010/03/11 11:33

S182	2	\$175 and photovoltaic adj devices and(slicing or dice\$3 or diced)and (ingot or wafer\$1 or semiconductor\$1 or IC or intergrated adj circuit)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/11 11:34
S183	2	S182 and @ad< "20040202"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/11 11:34
S184	2	S183 and(defects or variances or voids or defects or stacking adj faults or inclusions or impurities or grain or crystal adj boundaries or grain adj boundaries)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/11 11:37
S185	850	wafer\$1 adj identification	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/12 12:14
S186	1	S185 and etching and texturisation	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/12 12:14
S187	348	S185 and (etching or texturisation)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/12 12:15
S188	48	wafer\$1 adj identification same(imaging or cod or camera or CMOS or IR)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/12 12:16
S189	12	S188 and (etching or texturisation)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM TDB	OR	ON	2010/03/12 12:16

S190	0	S189 and phosphorus adj doping	US-PGPUB; USPAT; EPO; JPO; DERWENT; BM_TDB	OR	ON	2010/03/12 12:16
5191	0	S189 and phosphorus and doping	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/12 12:17
S192	8	S189 and @ad< "20040202"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/12 12:17
S193	0	S188 and phosphorus adj doping	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/12 12:21
3194	1323	phosphorus adji doping	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/12 12:21
3195	872	S194 and (etching or texturisation)	US-PGPUB; USPAT; EPO; JPO; DERWENT; BM_TDB	OR	ON	2010/03/12 12:21
S196	1	S195 and wafer\$1 adj identification and(imaging or ccd or camera or CMOS or IR)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/12 12:21
S197	29	S195 and identification and(imaging or ccd or camera or CMOS or IR)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/12 12:23

S198	16	S197 and @ad<"20040202"	US-PGPUB; USPAT; EPO; JPO; DERWENT; BM_TDB	OR	ON	2010/03/12 12:23
S199	0	S198 and edge adj etching	US-PGPUB; USPAT; BPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/12 12:23
\$200	14	S198 and edge and etching	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/12 12:23
S201	0	\$200 and oxide adj removal	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/12 12:24
S202	10	\$200 and oxide and removal	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/12 12:24
S203	1323	phosphorus adj doping	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/12 12:25
S204	898	\$203 and @ad<"20040202"	US-PGPUB; USPAT; EPO; UPO; DERWENT; IBM_TDB	OR	ON	2010/03/12 12:25
S205	8	\$204 and oxide adj removal	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/12 12:26

\$206	0	S205 and antireflective adj coating	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/12 12:26
S207	0	S205 and screen adj print	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/12 12:27
\$208	1	\$203 and inspect\$3 adj wafer\$1 and(cells or cell or memory)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/12 12:28
3209	1	\$203 and wafer\$1 adj identification and(imaging or cod or camera or CMOS or IR)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/12 12:29
\$210	566	wafer\$1 and screen adj print	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/12 12:29
211	15	S210 and antireflective adj coating	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/12 12:30
\$212	2	\$211 and @ad<"20040202"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/12 12:30
\$213	0	S198 and wafer adj image and cell adj image	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/12 12:34

\$214	1	\$203 and wafer adj image and cell adj image	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/12 12:34
2215	1	determining adj quality and wafer adj production and cell adj production and process	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/12 12:36
\$216	12	quality and wafer adj production and cell adj production and process	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/12 12:37
217	1	S216 and wafer adj image and cell adj image	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/12 12:37
218	2	S216 and identification and(imaging or cod or camera or CMOS or IR)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/12 12:37
219	0	S218 and @ad<"20040202"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/12 12:38
S220	8	S216 and @ad<"20040202"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/12 12:40
5221	22	Ingot adj production and wafer adj production	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM TDB	OR	ON	2010/03/16 11:52

S222	10	S221 and @ad<*20040202"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/16 11:53
223	0	Ingot adj production and wafer adj production same(slicing or dice\$3 or diced)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/16 12:07
3224	6	Ingot adj production same(slicing or dice\$3 or diced)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/16 12:07
\$225	4	S224 and @ad<"20040202"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/16 12:07
S226	0	S224 and cell adj inspect\$3	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/16 12:12
\$227	1	S221 and cell adj inspect\$3	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/16 12:12
S228	0	cell adj inspect\$3 and wafer adj production same(slicing or dice\$3 or diced)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/16 12:14
S229	0	cell adj inspect\$3 and wafer adj production and(slicing or dice\$3 or diced)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/16 12:14

\$230	22	icell adj inspect\$3 and(slicing or dice\$3 or diced)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/16 12:14
2231	6	\$230 and @ad<"20040202"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/16 12:18
232	0	cell adj inspect\$3 and imageing and(slicing or dice\$3 or diced)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/16 13:05
233	140	image\$3 and cell adj image and(slicing or dice\$3 or diced)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/16 13:06
\$234	0	\$233 and Ingot adj production same(slicing or dice\$3 or diced)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/16 13:06
235	0	\$233 and Ingot adj production and(slicing or dice\$3 or diced)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/16 13:07
S236	2	"6140140".pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/16 14:52
\$237	23	cell adj inspect\$3 and(slicing or dice\$3 or diced)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM TDB	OR	ON	2010/03/27 17:19

S238	6	\$237 and @ad<"20040202"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/27 17:19
S239	3	S238 and (breakage or damage)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/27 17:21
S240	64	photovoltaic adj devices and(slicing or dice\$3 or diced)and ingot	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/27 17:23
S241	55	\$240 and(defects or variances or voids or defects or stacking adj faults or inclusions or impurities or grain or crystal adj boundaries)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/27 17:23
S242	20	S241 and @ad<"20040202"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/27 17:24
S243	3	S242 and breakage	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/27 17:25
S244	2	\$237 and(compar\$3 or match\$3)and breakage	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/27 17:36
S245	1	S244 and @ad<"20040202"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM TDB	OR	ON	2010/03/27 17:37

S246	4764	crystallographic adj structure	US PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/27 17:37
S247	110	\$246 and(compar\$3 or match\$3)and breakage	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/27 17:37
S248	65	\$247 and @ad<"20040202"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/27 17:38
S249	2	"7144457".pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/27 17:44
S250	0	\$249 and(compar\$3 or match\$3)and breakage	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/27 17:44
\$251	0	\$249 and breakage	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/27 17:44
S252	2	*6465781*.pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/27 17:45
S253	0	\$252 and breakage	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/27 17:45

S254	4764	crystallographic adj structure	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/27 17:46
\$255	1	\$254 and wafer adj image and cell adj image	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/27 17:46
\$256	1110	(("(4352948") or ("6161054") or ("5203005") or ("5287472") or ("5292677") or ("5485097") or ("6243308") or ("4435498") or ("4471483") or ("4493055") or ("4519035") or ("4549444") or ("4898835") or ("4999689") or ("5019736") or ("5024972") or ("5252507") or ("5265847") or ("5315130") or ("5362666") or ("5393617") or ("5478363") or ("569471") or ("5566392") or ("5657284") or ("5552243") or ("5698492") or ("569847") or ("5716459") or ("569847") or ("5698453") or ("5698342") or ("5716459") or ("620678") or ("6101140") or ("6161213") or ("6225167") or ("6330819") or ("4304641") or ("4338480") or ("4353160") or ("4385198") or ("4400221") or ("4400868") or (").pn.")).	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2010/03/27 17:47
\$257	106	\$256 and @ad< 20040202"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/27 17:47
258	5	\$257 and inspect\$3 and(crystallographic adj structure or wafer or ingot or cells or cell)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/27 17:47
3259	4	\$258 and(compar\$3 or match\$3)and(solar adj cell or cell crystallographic adj structure or wafer or ingot or cells or cell)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/27 17:47
260	5	\$257 and inspect\$3 and(crystallographic adj structure or wafer or ingot or cells)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/27 17:47

S261	0	\$260 and(compar\$3 or match\$3)and breakage	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/27 17:48
\$262	0	\$260 and breakage	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/27 17:48
\$263	142	image\$3 and cell adj image and(slicing or dice\$3 or diced)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/27 17:48
\$264	6	\$263 and(compar\$3 or match\$3)and breakage	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/27 17:48
<b>2</b> 65	2	\$264 and @ad< "20040202"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/27 17:49
<b>3</b> 266	110	\$246 and(compar\$3 or match\$3)and breakage	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/27 17:50
\$267	65	\$266 and @ad<"20040202"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/27 17:50
268	66	\$267 cell adj image and wafer adj image and(compar\$3 or match\$3)and breakage	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM TDB	OR	ON	2010/03/27 17:51

S269	66	\$267 cell adj image and wafer adj image same(compar\$3 or match\$3)same breakage	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/27 17:51
270	65	\$269 and @ad< "20040202"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/27 17:51
271	2	*5667597*.pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/27 17:55
\$272	0	S271 and breakage	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/27 17:55
273	2	"6316832".pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/27 17:56
274	2	S273 and breakage	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/27 17:56
S275	4764	\$254 cell adj image and wafer adj image and(compar\$3 or match\$3)and breakage	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/27 17:57
\$276	1	\$254 and cell adj image and wafer adj image and(compar\$3 or match\$3) and breakage	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM TDB	OR	ON	2010/03/27 17:58

\$277	2	"5716459".pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/27 17:58
S278	0	S277 and breakage	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/27 17:59
\$279	2	"5153444".pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/27 17:59
\$280	0	S279 and breakage	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/27 17:59
\$281	535	crystallographic adj structure and(wafer or ingot)and section	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/27 18:01
S282	1	\$281 and cell adj image same wafer adj image same(compar\$3 or match\$3) same breakage	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/27 18:01
\$283	2	"7144457".pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/27 18:02
S284	0	S283 and(breakage or damaged)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/27 18:03

\$285	42	\$254 and inspect\$3 and(compar\$3 or match\$3)and wafer and(solar adj cell or cell or memory)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/27 18:08
286	13	\$285 and @ad< "20040202"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/27 18:08
\$287	0	S286 and breakage	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/27 18:08
\$288	535	crystallographic adj structure and(wafer or ingot) and section	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/27 18:09
\$289	162	\$288 and analyz\$3 and(crystalline or crystallographic adj structure)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/27 18:09
290	120	S289 and(imaging or cod or camera or CMOS or IR)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/27 18:09
S291	48	\$290 and @ad<"20040202"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/27 18:09
S292	0	S291 and(breakage or damaged)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/27 18:09

\$293	2491	ingot and production adj process	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/27 18:11
S294	525	\$293 and wafer\$3 and production adj process	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/27 18:11
\$295	128	\$294 and cell and production adj process	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/27 18:11
S296	75	\$295 and @ad<"20040202"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/27 18:11
\$297	75	\$296 and(memory or cell or memory adj cell or die)and wafer\$1	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/27 18:11
S298	12	\$297 and(imaging or cod or camera or CMOS or IR)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/27 18:11
5299	10	\$298 and(compar\$3 or match\$3)and(memory or cell or memory adj cell or die) and wafer\$1	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/27 18:11
5300	10	\$299 and @ad<"20040202"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM TDB	OR	ON	2010/03/27 18:11

S301	6	S300 and(breakage or damaged)	us Pgpub; uspat; epo; Jpo; derwent; [BM_TDB	OR	ON	2010/03/27 18:11
S302	2	S300 and breakage	US-POPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/27 18:17
S303	2	*6140140",pn.	US-POPUB; USPAT; EPO; JPO; DERWENT; BM_TDB	OR	ON	2010/03/27 18:31
S304	1	S303 and memory	US-POPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/27 18:32
S305	2	*5757474*,pn.	US-POPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/27 21:51
S306	0	S305 and(breakage or damage)	US-POPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/27 21:56
S307	2	*5757474*.pn.	US-PCPUB; USPAT; EPO; JPO; DERWENT; BM_TDB	OR	ON	2010/03/29 10:00
S308	2	*6482661*,pn.	US-POPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/03/29 10:01

S309	1111	[("(4352948") or ("5161054") or ("5203005") or ("5287472") or ("5292677") or ("5485097") or ("6243308") or ("4435498") or ("4471483") or ("44393055") or ("4519035") or ("45434444") or ("4898835") or ("4999689") or ("5019736") or ("5024972") or ("5252507") or ("5265847") or ("5315130") or ("536666") or ("5393617") or ("5478363") or ("5539964") or ("5539964") or ("5694919") or ("5624771") or ("5666392") or ("5697284") or ("5698453") or ("5698342") or ("5716459") or ("5808947") or ("5698453") or ("581693") or ("5926419") or ("6040912") or ("F826644") or ("6040678") or ("6140140") or ("6161213") or ("6225167") or ("6330819") or ("4304641") or ("4338480") or ("4353160") or ("4385198") or ("4400221") or ("4400868") or (").pn.")).	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2010/03/29 10:02
\$310	0	(*product\$3samesolaradjcells*).PN.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2010/10/15 10:16
3311	28478	product\$3 same solar adjc ells	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/10/15 10:16
3312	9636	product\$3 same solar adj cells	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/10/15 10:16
3313	1	\$312 and establish\$3 adj correspondence same wafers same solar adj cell	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/10/15 10:18
3314	3	\$312 and establish\$3 adj correspondence and wafers and solar adj cell	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/10/15
3315	106	crystallographic adj structure and wafer\$1 and solar adj cells	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/10/15 10:20

S316	5	S315 and matrix same solar adj cells	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/10/15 10:21
3317	1	\$314 and solar adj cell and produced and treating and silicon adj wafer\$1	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/10/15 10:23
S318	507	solar adj cell and produced and treating and silicon adj wafer\$1	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/10/15 10:23
S319	34	matrix same solar adj cells and produced and treating and silicon adj wafer \$1	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/10/15 10:24
S320	2	\$319 and silicon adj wafer\$1 and cutt\$3 and ingot	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/10/15 10:26
S321	0	\$320 and @ad< "20040202"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/10/15 10:26
S322	5030	solar adj cells and silicon adj wafer\$1	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/10/15 10:36
S323	0	solar adj cells and silicon adj wafer\$1 same solar adj cell adj traceability	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/10/15 10:36

S324	1	solar adj cells and silicon adj wafer\$1 and solar adj cell adj traceability	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/10/15 10:36
S325	9636	product\$3 same solar adj cells	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/10/15 10:38
S326	8	S325 and crystallographic adj structure and wafer\$1 and solar adj cells	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/10/15 10:39
S327	18	solar adj cells and silicon adj wafer\$1 and traceability	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/10/15 10:48
S328	5	\$327 and @ad<*20040202"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/10/15 10:48
S329	72405	(compar\$3 or match\$3)and wafer\$1 and(solar adj cells or cell)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/10/15 10:57
S330	2509	(compar\$3 or match\$3)same wafer\$1 same(solar adj cells cell)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/10/15 10:57
S331	3	\$330 and matrix same solar adj cells and produced and treating and silicon adj wafer\$1	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM TDB	OR	ON	2010/10/15 10:58

S332	0	\$331 and @ad<"20040202"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/10/15 10:58
S333	1	image\$3 adj device and crystallographic adj structure and wafer and cell	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/10/15 11:02
S334	429	crystallographic adj structure and wafer and cell	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/10/15 11:03
S335	5	\$334 and(compar\$3 or match\$3)same wafer\$1 same(solar adj cells or cell or matrix)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/10/15 11:03
S336	3	\$335 and @ad<"20040202"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/10/15 11:03
\$337	0	\$336 and(image\$3 adj device or camera or cod)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/10/15 11:23
S338	106	\$334 and(image\$3 adj device or camera or ccd)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/10/15 11:23
S339	32	S338 and @ad<"20040202"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/10/15 11:23

S340	0	\$339 and(compar\$3 or match\$3)same wafer\$1 same(solar adj cells or cell or matrix)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/10/15 11:23
S341	27	\$339 and(compar\$3 or match\$3)and wafer\$1 and(solar adj cells or cell or matrix)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/10/15 11:24
S342	0	S341 and matrix same solar adj cells and produced and treating and silicon adj wafer\$1	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/10/15 11:24
\$343	1	S341 and matrix and solar adj cells and produced and treating and silicon adj wafer\$1	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/10/15 11:24
3344	345	S334 and(defects or variances or voids or defects or stacking adj faults or inclusions or impurities or grain or crystal adj boundaries or breakage)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/10/15 11:36
345	86	\$344 and(image\$3 adj device or camera or cod)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/10/15 11:37
S346	78	\$345 and(compar\$3 or match\$3)and wafer\$1 and(solar adj cells or cell or imatrix)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/10/15 11:37
5347	0	S346 and defect same breakage	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM TDB	OR	ON	2010/10/15 11:38

S348	6	S346 and defect and breakage	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/10/15 11:38
S349	25	S346 and @ad< "20040202"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/10/15 11:39
\$350	0	\$334 and(compar\$3 or match\$3)and wafer\$1 and(solar adj cells or cell or matrix)and(software or program)and image adj recognition and detect adj defect and breakage	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/10/15 11:44
S351	0	(compar\$3 or match\$3)and wafer\$1 and(solar adj cells or cell or matrix)and (software or program)and image adj recognition and detect adj defect and breakage	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/10/15 11:44
\$352	0	S334 and(software or program)and image adj recognition and detect adj defect and breakage	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/10/15 11:46
S353	1	(software or program) and image adj recognition and detect adj defect and breakage	US-PGPUB; USPAT; EPO; JPO; DERWENT; BM_TDB	OR	ON	2010/10/15 11:46
3354	3350	crystallographic adj structure and(produc\$4 or obtaining)and(cell adj image or cells or cell or wafer or memory)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/10/15 11:47
3355	0	S354 and(software or program)and image adj recognition and detect adj defect and breakage	US-PGPUB; USPAT; EPO; UPO; DERWENT; IBM TDB	OR	ON	2010/10/15 11:48

S356	0	S354 and image adj recognition and detect adj defect and breakage	US-PGPUB; USPAT; EPO; JPO; DERWENT; BM_TDB	OR	ON	2010/10/15 11:48
S357	0	S334 and image adj recognition and detect adj defect and breakage	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/10/15 11:48
S358	0	inspect\$3 and(compar\$3 or match\$3)and wafer\$1 and(solar adj cells or cell or matrix)and(software or program)and image adj recognition and detect adj defect and breakage	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/10/15 11:53
S359	0	inspect\$3 adj solar adj cell same wafer\$1 adj cell	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/10/15 11:54
S360	5	inspect\$3 and solar adj cell same wafer\$1 adj cell	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/10/15 11:54
S361	0	S360 and @ad<"20040202"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/10/15 11:54
S362	2	"5257544".pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/10/15 12:02
S363	0	\$360 and @ad<"20040202"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/10/15 12:06

S364	2	° 6760472".pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/10/15 12:21
3365	2	\$364 and @ad<"20040202"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/10/15 12:22
3366	2	"20080160648"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/10/21 09:22
3367	1	S366 and software	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/10/21 09:22
3368	1237	micro adj defects and(semiconductors or wafer\$1)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/10/21 11:21
3369	5	\$368 and Ingot adj production and(slicing or dice\$3 or diced)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/10/21 11:22
3370	2	\$369 and (@ad<"20040202" or @rlad<"20040202" or @prad<"20040202" or @ptad<"20040202" or @ptad<"20040202")	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/10/21 11:22
3371	2	\$369 and @ad<"20040202"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM TDB	OR	ON	2010/10/21 11:23

S372	0	\$371 and inspect\$3 and(crystallographic adj structure or wafer or ingot or cells)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/10/21 11:23
S373	0	S371 and(compar\$3 or match\$3)same wafer same(solar adj cell or cell)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/10/21 11:24
S374	584	detect\$3 and micro adj defects and(semiconductors or wafer\$1)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/10/21 11:25
S375	162	S374 and(compar\$3 or match\$3)and (memory or cell or memory adj cell)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/10/21 11:25
S376	96	\$375 and @ad< "20040202"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/10/21 11:26
S377	46	\$374 and(compar\$3 or match\$3)same(memory or cell or memory adj cell)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/10/21 11:27
S378	246	\$374 and(compar\$3 or match\$3)same(memory or cell or memory adj cell or wafer\$1)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/10/21 11:28
S379	145	\$378 and @ad<"20040202"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/10/21 11:28

S380	2	\$379 and(compar\$3 or match\$3)same wafer same(solar adj cell or cell)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/10/21 11:28
S381	0	S379 and(imaging or cod or camera or CMOS or IR)same wafer adj image same cell adj image	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/10/21 11:32
S382	0	S374 and(imaging or cod or camera or CMOS or IR)same wafer adj image same cell adj image	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/10/21 11:32
S383	0	S368 and(imaging or cod or camera or CMOS or IR)same wafer adj image same cell adj image	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/10/21 11:33
S384	650	detect\$3 and micro adj defects and(semiconductors or wafer\$1 or silicon oer insulator adj wafer\$1 or polycrystalline adj silicon)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/10/21 11:37
S385	650	detect\$3 and micro adj defects and(semiconductors or wafer\$1 or silicon or insulator adj wafer\$1 or polycrystalline adj silicon)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/10/21 11:37
S386	313	\$385 and @ad< "20040202"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/10/21 11:37
S387	0	\$386 and(imaging or ccd or camera or CMOS or IR)same wafer adj image same cell adj image	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM TDB	OR	ON	2010/10/21 11:38

S388	124	S386 and(imaging or ccd or camera or CMOS or IR)captur\$4 same wafer adj image same cell adj image	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/10/21 11:39
S389	61	S388 and(breakage or damaged)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/10/21 11:41
S390	0	S389 and producing same wafer adj image same cell adj image	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/10/21 11:44
S391	0	S385 and producing same wafer adj image same cell adj image	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/10/21 11:44
S392	0	S385 and crystallographic adj structure and wafer and ingot	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/10/21 11:45
3393	44	crystallographic adj structure and wafer and ingot	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/10/21 11:46
S394	19	\$393 and(imaging or cod or camera or CMOS or IR)captur\$4 same wafer adj image same cell adj image	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/10/21 11:46
S395	0	S394 and producing same wafer adj image same cell adj image	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/10/21 11:46

S396	0	\$394 and producing and wafer adj image same cell adj image	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/10/21 11:46
S397	0	S394 and (producing or obtaining or generat\$3)and wafer adj image same cell adj image	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/10/21 11:47
S398	1	\$394 and(compar\$3 or match\$3)same wafer same(solar adj cell or cell)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/10/21 11:47
S399	6	S394 and @ad<"20040202"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/10/21 11:48
S400	0	\$399 and(compar\$3 or match\$3)same wafer same(solar adj cell or cell)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/10/21 11:48
S401	0	\$399 and(compar\$3 or match\$3)and wafer and(solar adj cell or cell)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/10/21 11:48
S402	0	S398 and @ad<"20040202"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/10/21 12:56
S403	1734	136/249,262,243,252,246.OQLS.	USPAT	OR	ON	2010/10/21 13:05
S404	1674	382/145, 141. CCLS.	USPAT	OR	ON	2010/10/21 13:06
S405	2037	356/72,237.1,30.COLS.	USPAT	OR	ON	2010/10/21 13:09

S406	8829	438/381,396,933,48,57,73,74,93,94,970,584,585,586.CQLS.	USPAT	OR	ON	2010/10/21 13:12
S407	6253	365/201,63.CCLS.	USPAT	OR	ON	2010/10/21 13:14
S408	5009	429/185,162,210,90,217,218.1,337,59,157,223.OQLS.	USPAT	OR	ON	2010/10/21 13:17
S410	9076	257/461,414,428,431,461,E27.089,E27.001,E27.009,E27.01,E27.07,E27.081, E27.084,E27.085,E27.086,E27.089,E27.081,E27.098,E27.101,257,E27.122, E27.127,E27.128,E31.001,E31.111,E31.113,E31.114,E31.115,CQLS.	USPAT	OR	ON	2010/10/21 13:27
S411	1905	204/252,193,194,242,252.COLS.	USPAT	OR	ON	2010/10/21 13:31
S412	5166	WAFER SAME SOLAR SAME CELL\$1	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/10/21 14:40
S413	113	S412 SAME IMAGE\$1	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/10/21 14:41
S414	14	S413 SAME (MATCH\$3 OR COMPAR\$4)	US-PGPUB; USPAT; EPO; JPO; DERWENT; BM_TDB	OR	ON	2010/10/21 14:42
\$415	2	S414 and (@ad<"20040202" or @rlad<"20040202" or @prad<"20040202" or @ptad< "20040202")	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/10/21 14:42
S416	2	S414 and @ad< "20040202"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/10/21 14:42
3417	1734	136/249,262,243,252,246.CQLS.	USPAT	OR	ON	2010/10/21 15:41
3418	1674	382/145,141.0Q.S.	USPAT	OR	ON	2010/10/21 15:41

S419	2037	356/72,237.1,30.COLS.	USPAT	OR	ON	2010/10/21 15:42
5420	8829	438/381,396,933,48,57,73,74,93,94,970,584,585,586.CCLS.	USPAT	OR	ON	2010/10/21 15:42
S421	6253	365/201,63.CCLS.	USPAT	OR	ON	2010/10/21 15:42
S422	5009	429/185,162,210,90,217,218.1,337,59,157,223.OQLS.	USPAT	OR	ON	2010/10/21 15:42
S423	9076	257/461,414,428,431,461,E27,089,E27,001,E27,009,E27,01,E27,07,E27,081, E27,084,E27,085,E27,086,E27,089,E27,081,E27,098,E27,101,257,E27,122, E27,127,E27,128,E31,001,E31,111,E31,113,E31,114,E31,115,CQLS.	USPAT	OR	ON	2010/10/21 15:42
S424	1905	204/252,193,194,242,252.CQLS.	USPAT	OR	ON	2010/10/21 15:42
S425	243	\$417 and WAFER SAME SOLAR SAME CELL\$1	USPAT	OR	ON	2010/10/21 15:43
S426	22	S425 and IMAGE\$1	USPAT	OR	ON	2010/10/21 15:45
S427	21	S426 and (MATCH\$3 OR COMPAR\$4)	USPAT	OR	ON	2010/10/21 15:45
S428	18	\$427 and @ad<"20040202"	USPAT	OR	ON	2010/10/21 15:46
S429	6	S428 and (imaging or ccd or camera or CMOS or IR)	USPAT	OR	ON	2010/10/21 15:51
S430	0	\$429 and(producing or obtaining or generat\$3)and wafer adj image same cell adj image	USPAT	OR	ON	2010/10/21 15:53
S431	0	S418 and WAFER SAME SOLAR SAME CELL\$1	USPAT	OR	ON	2010/10/21 15:54
S432	3	S418 and WAFER and SOLAR and CELL\$1	USPAT	OR	ON	2010/10/21 15:54
S433	5	S419 and WAFER and SOLAR and CELL\$1	USPAT	OR	ON	2010/10/21 15:56
S434	4	S433 and (MATCH\$3 OR COMPAR\$4)	USPAT	OR	ON	2010/10/21 15:57
S435	0	\$434 and(producing or obtaining or general\$3)and wafer adj image same cell adj image	USPAT	OR	ON	2010/10/21 15:57
S436	2	S434 and (imaging or cod or camera or CMOS or IR)	USPAT	OR	ON	2010/10/21 15:58

S437	297	S420 and WAFER and SOLAR and CELL\$1	USPAT	OR	ON	2010/10/21 16:03
S438	218	S437 and (MATCH\$3 OR COMPAR\$4)	USPAT	OR	ON	2010/10/21 16:03
S439	0	\$438 and(producing or obtaining or generat\$3)and wafer adj image same coll adj image	USPAT	OR	ON	2010/10/21 16:03
S440	51	S438 and (imaging or cod or camera or CMOS or IR)	USPAT	OR	ON	2010/10/21 16:04
S441	196	\$438 and(compar\$3 or match\$3)and(solar adj cell or cell crystallographic adj structure or wafer or ingot or cells or cell)	USPAT	OR	ON	2010/10/21 16:05
S442	27	\$441 and(compar\$3 or match\$3)same wafer same(solar adj cell or cell)	USPAT	OR	ON	2010/10/21 16:06
S443	23	S442 and(@ad<"20040202" or @riad<"20040202" or @prad<"20040202" or @prad<"20040202" or @prad<"20040202"	USPAT	OR	ON	2010/10/21 16:06
S444	20	S442 and @ad<"20040202"	USPAT	OR	ON	2010/10/21 16:07
S445	1	S444 and(imaging or ccd or camera or CMOS or IR)	USPAT	OR	ON	2010/10/21 16:08
S446	1	S421 and WAFER and SOLAR and CELL\$1	USPAT	OR	ON	2010/10/21 16:14
S447	21	S422 and WAFER and SOLAR and CELL\$1	USPAT	OR	ON	2010/10/21 16:14
S448	2	S447 and (imaging or ccd or camera or CMOS or IR)	USPAT	OR	ON	2010/10/21 16:15
S449	0	\$448 and(compar\$3 or match\$3)same wafer same(solar adj cell or cell)	USPAT	OR	ON	2010/10/21 16:15
S450	247	S423 and WAFER and SOLAR and CELL\$1	USPAT	OR	ON	2010/10/21 16:16
S451	69	S450 and(imaging or ccd or camera or CMOS or IR)	USPAT	OR	ON	2010/10/21 16:16
S452	3	S451 and(compar\$3 or match\$3)same wafer same(solar adj œll or cell)	USPAT	OR	ON	2010/10/21 16:16
S453	13	S424 and WAFER and SOLAR and CELL\$1	USPAT	OR	ON	2010/10/21 16:17
S454	2	S453 and(imaging or cod or camera or CMOS or IR)	USPAT	OR	ON	2010/10/21 16:17

S455	1	S454 and(compar\$3 or match\$3)same wafer same(solar adj cell or cell)	USPAT	OR	ON	2010/10/21 16:17
S458	2	"5757474".pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/11/13 16:51

## EAST Search History (Interference)

Ref#	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S456		(WAFER and SOLAR adj CELL\$1 and sectioning and manufacturing and silicon adj ingot and imaging and(compar\$3 or match\$3)and wafer and(solar adj cell or cell)).CLM.	US-PGPUB; USPAT; UPAD	OR	ON	2010/10/21 16:33
S457		(WAFER and SOLAR adj CELL\$1 and imaging and(compar\$3 or match\$3) and wafer and(solar adj cell or cell)).O.M.	US-PGPUB; USPAT; UPAD	OR	ON	2010/10/21 16:34

## 11/22/10 9:55:29 AM

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